Cobalt silicide has emerged as a leading contact material in silicon technology due to its low resistivity, high stability and small lattice mismatch. Low-resistivity polycrystalline cobalt disilicide (CoSi2) has many favorable properties, such as low bulk electrical resistivity and good lattice match with Si (001), and has been widely used as a contact material for silicon ULSI (ultra-large scale integration) devices as the device feature size decreases.

Quick Facts

- **Product**: Cobalt Silicide Powder
- **Color**: Gray Powder
- **Stock No**: NS6130-12-000244
- **CAS**: 12017-12-8
- **Purity**: 99.9%
- **APS**: 40-50μm
- **Other Metal**: 900ppm
Cobalt Silicide Powder

Applications

✓ Ultra-fast Metal-Semiconductor-Metal photodetector
✓ High frequency Schottky Junction Transistors

Technical Specification

<table>
<thead>
<tr>
<th>Molecular Formula</th>
<th>Molecular Weight</th>
<th>Density</th>
<th>Melting Point</th>
</tr>
</thead>
<tbody>
<tr>
<td>CoSi2</td>
<td>115.1 g/mol</td>
<td>5.3 g/cm³</td>
<td>1277 °C</td>
</tr>
</tbody>
</table>

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